## 10/562098 JC10 Rec'd PCT/PTO 21 DEC 2005

## Amendments to and listing of the Claims:

Please amend claims 3-8 as follows. This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Original) A resin composition for stereolithography, which is an actinic radiation-curable resin composition comprising:

a cationic-polymerizable organic compound;

a radical-polymerizable organic compound;

a photo initiator for cationic polymerization; and

a photo initiator for radical polymerization,

wherein the photo initiator for cationic polymerization comprises a compound represented by the following formula (I), the compound having a purity of 80% or higher:

wherein M represents an antimony atom or a phosphorus atom; and the broken line between S<sup>+</sup> and MF<sub>6</sub><sup>-</sup> represents an ionic bond.

- 2. (Original) The resin composition for stereolithography as claimed in claim 1, wherein the purity of the compound represented by the formula (I) is 90% or higher.
- 3. (Currently Amended) The resin composition for stereolithography as claimed in claim 1 [[or 2]], wherein the purity of the compound represented by the formula (I) is 95% or higher.
- 4. (Currently Amended) The resin composition for stereolithography as claimed in any of claims 1 to 3 claim 1, wherein M in the compound represented by the formula (I) is an antimony atom.

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- 5. (Currently Amended) The resin composition for stereolithography as claimed in any of claims 1 to 4 claim 1, wherein the cationic-polymerizable organic compound comprises at least one compound having an epoxy group.
- 6. (Currently Amended) The resin composition for stereolithography as claimed in any of claims 1 to 5 claim 1, wherein the radical-polymerizable organic compound comprises at least one compound having a (meth)acryl group.
- 7. (Currently Amended) The resin composition for stereolithography as claimed in any of claims 1 to 6 claim 1, which comprises an oxetane compound at a ratio of from 1 to 30% by mass with respect to the mass of the cationic-polymerizable organic compound.
- 8. (Currently Amended) The resin composition for stereolithography as claimed in any of claims 1 to 7 claim 1, which comprises a polyalkylene ether compound at a ratio of from 1 to 30% by mass with respect to the mass of the cationic-polymerizable organic compound.